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and Instrumentation in Particle Physics  
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*“Instrumentation  
as enabler of Science”*

# Silicon Sensors for High Luminosity Trackers RD50 Status Report

TIPP '14  
03.06.2014

Susanne Kuehn, Albert-Ludwigs-University Freiburg  
On behalf of the RD50 Collaboration

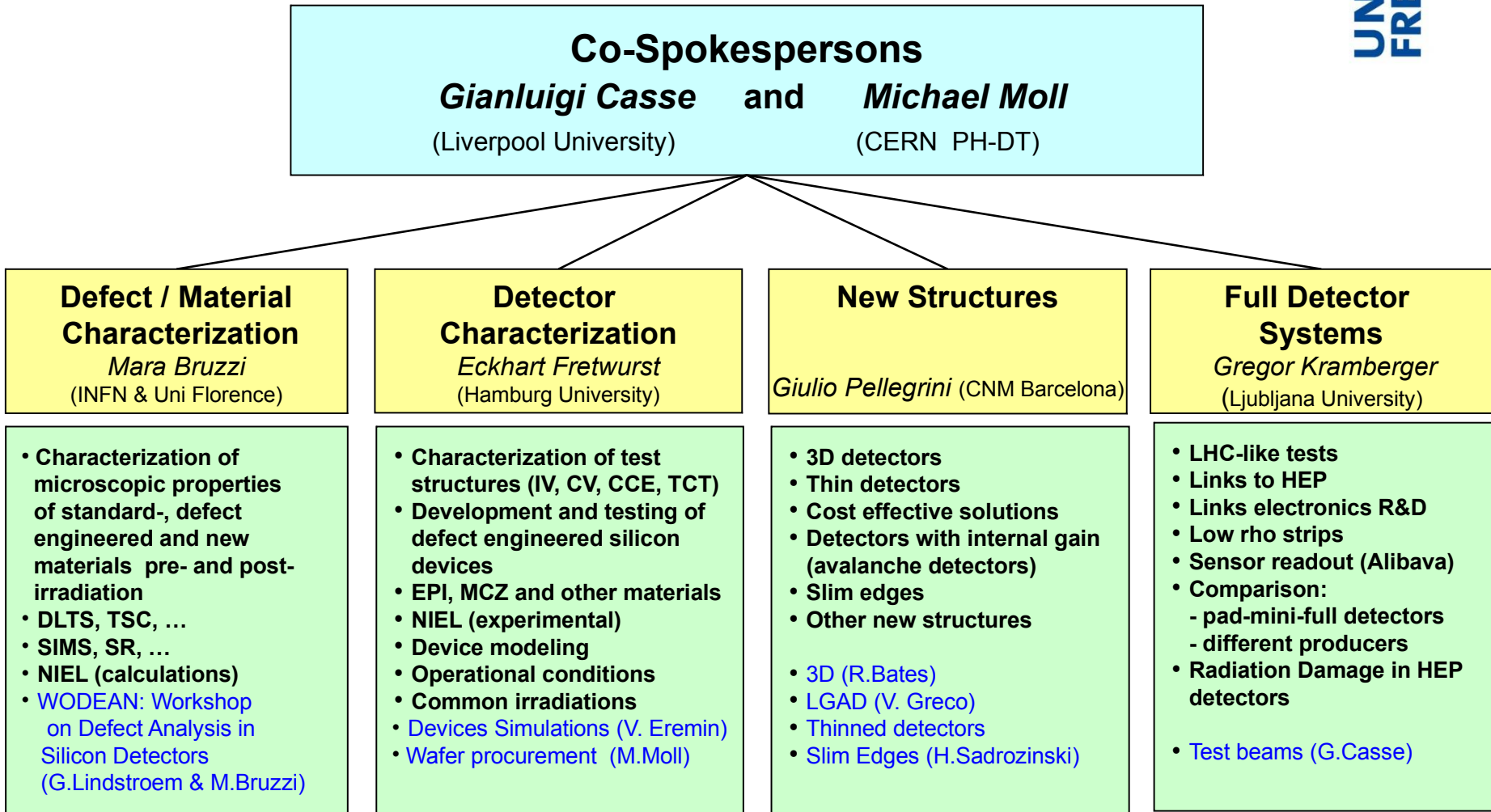
**RD50** - Radiation hard semiconductor devices for very high luminosity colliders



UNI  
FREIBURG

- Introduction
- Results from (selected) Research Fields of the RD50 Collaboration
- Achievements and Findings for LHC Experiments
- Summary

Only a selection on interesting topics, the full variety of RD50 can be found on:  
<http://rd50.web.cern.ch/rd50/>



Collaboration Board Chair & Deputy: G.Kramberger (Ljubljana) & J.Vaitkus (Vilnius), Conference committee: U.Parzefall (Freiburg)  
CERN contact: M.Moll (PH-DT), Secretary: V.Wedlake (PH-DT), Budget holder & GLIMOS: M.Glaser (PH-DT)

## 41 European institutes

**Belarus** (Minsk), **Belgium** (Louvain), **Czech Republic** (Prague (3x)), **Finland** (Helsinki, Lappeenranta ), **France** (Paris), **Germany** (DESY, Dortmund, Erfurt, Freiburg, Hamburg, Karlsruhe, Munich(2x)), **Greece** (Demokritos), **Italy** (Bari, Florence, Perugia, Pisa, Torino), **Lithuania** (Vilnius), **Netherlands** (NIKHEF), **Poland** (Krakow, Warsaw(2x)), **Romania** (Bucharest (2x)), **Russia** (Moscow, St.Petersburg), **Slovenia** (Ljubljana), **Spain** (Barcelona(2x), Santander, Valencia), **Switzerland** (CERN, PSI), **Ukraine** (Kiev), **United Kingdom** (Glasgow, Liverpool)

## 6 North-American institutes

**Canada** (Montreal), **USA** (BNL, Fermilab, New Mexico, Santa Cruz, Syracuse)

**1 Middle East institute** **Israel** (Tel Aviv)

**1 Asian institute** **India** (Delhi)



14<sup>th</sup> Workshop  
in Freiburg, 2009

**Collaborators from several experiments at the LHC: ATLAS, CMS and LHCb and also from ILC**  
→ Cross-experiment discussions

→ **49 institutes and 275 members**

**+ 21 observers**

→ **Workshops**

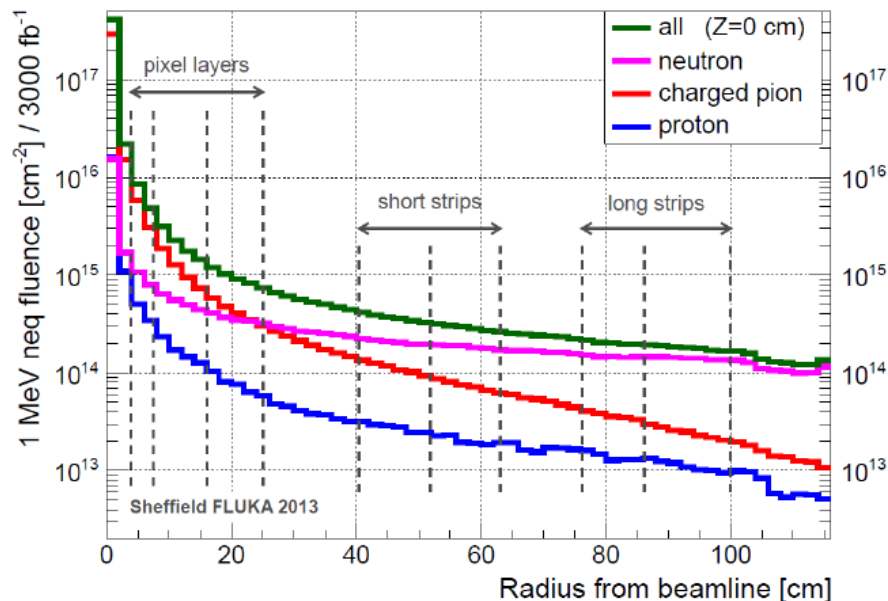
→ **Irradiation facilities**

More details on: <http://rd50.web.cern.ch/rd50/>

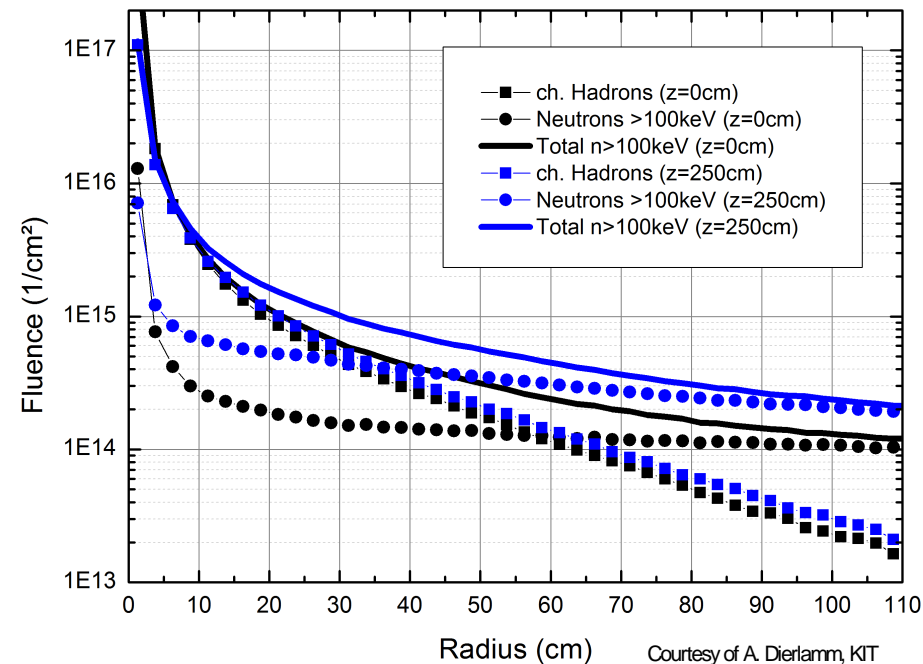
# Challenge: Radiation Damage in the upgrade of LHC

Planned upgrade of the LHC to HL-LHC (and beyond HE-LHC, VHE-LHC)  
 For HL-LHC in  $\sim 2023$ :  $3000 \text{ fb}^{-1}$  expected integrated luminosity

Expected particle fluences for the ATLAS Inner tracker:



the CMS tracker:

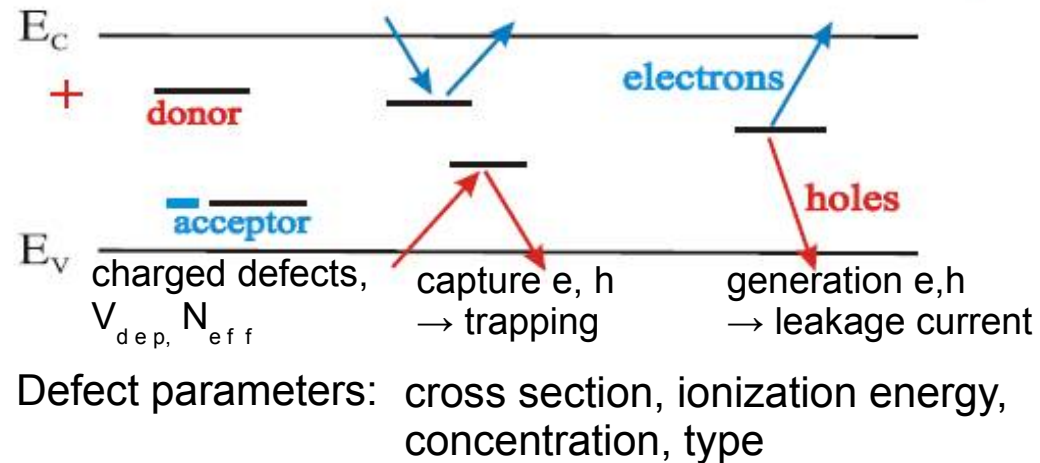


I. Dawson, P. S. Miyagawa, Sheffield University, Atlas Upgrade radiation background simulations

Courtesy of A. Dierlamm, KIT

- Pixel damage due to neutrons and pions, strips mainly due to neutrons
- Exposure up to  $1 \cdot 10^{16} \text{ neq/cm}^2$
- **Investigation and understanding of radiation damage of sensors needed**

- Generation of defects depending on incident particle type and energy
- Goal: Identify defects causing change of detector properties, namely trapping, leakage current and  $N_{eff}(V_{dep})$ 
  - use knowledge for device engineering and input to simulations



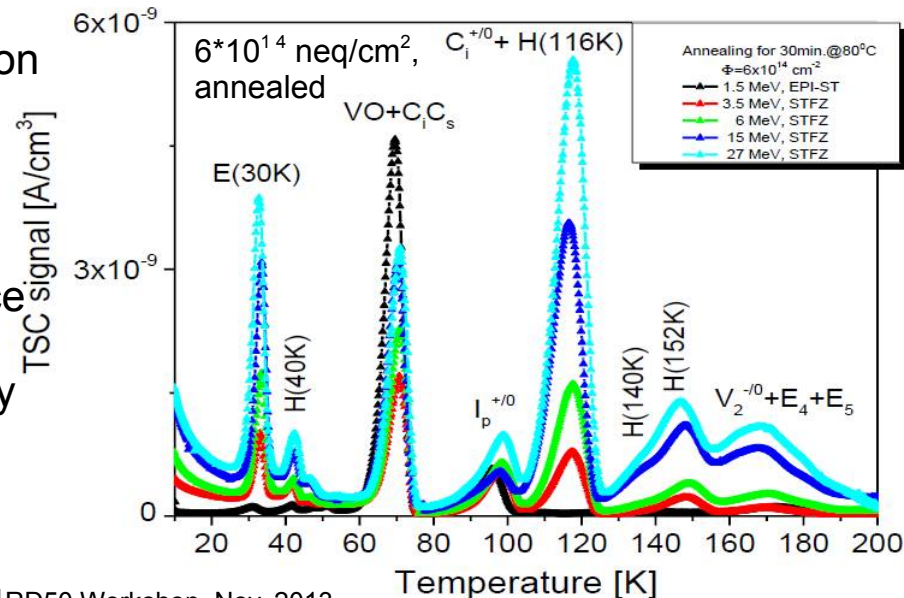
- Work: Defect Analysis on many identical samples performed with the various tools in RD 50 Collaboration

- C-DLTS (Capacitance Deep Level Transient Spectroscopy)
- I-DLTS (Current Deep Level Transient Spectroscopy)
- TCT (Transient Charge Technique)
- TSC (Thermally Stimulated Current)
- CV/IV (Capacity/Voltage vs. Current) ..

- Tests after irradiation with protons, neutrons, electrons and  $^{60}\text{Co}$ -gammas

TSC measurement on defects after electron irradiation

dependence on electron energy



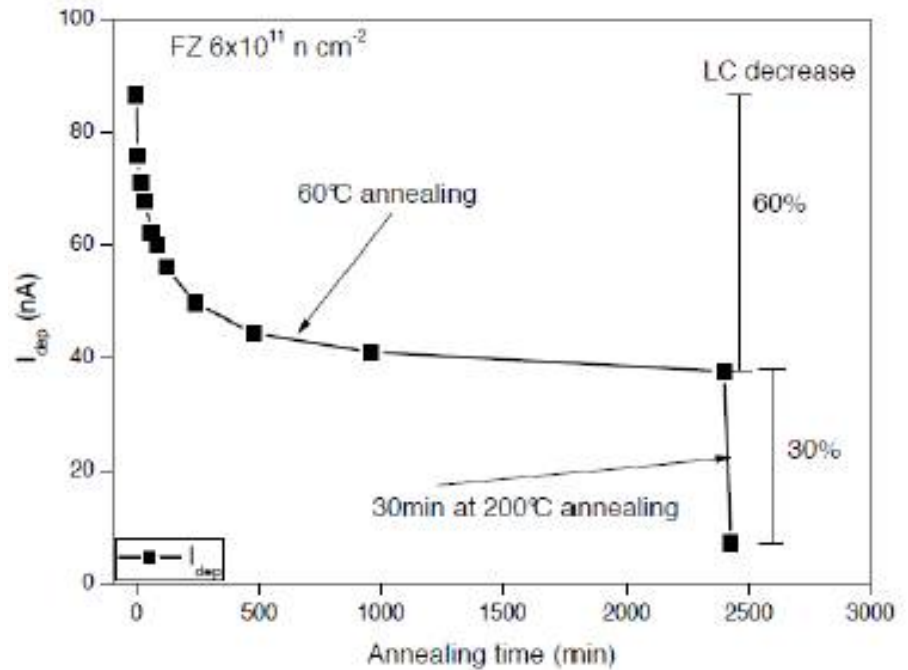
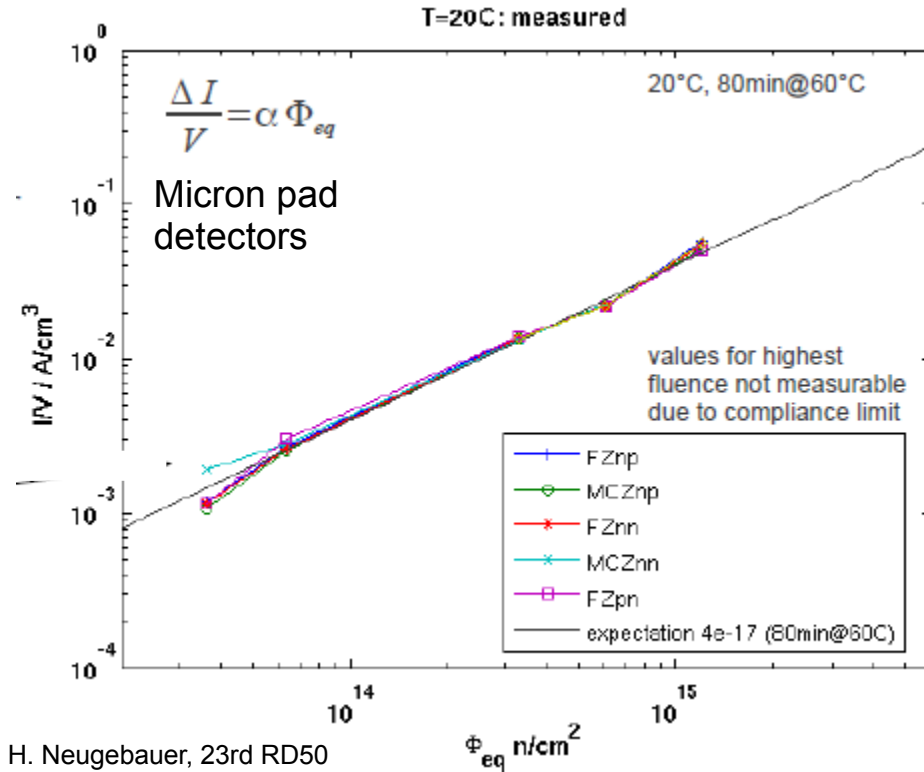


# Impact of Defects: Change of $I_{leak}$

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- Dependence of leakage current on material

- Dependence on annealing



H. Neugebauer, 23rd RD50 Workshop Nov. 2013

A. Junkes PoS(Vertex2011)035

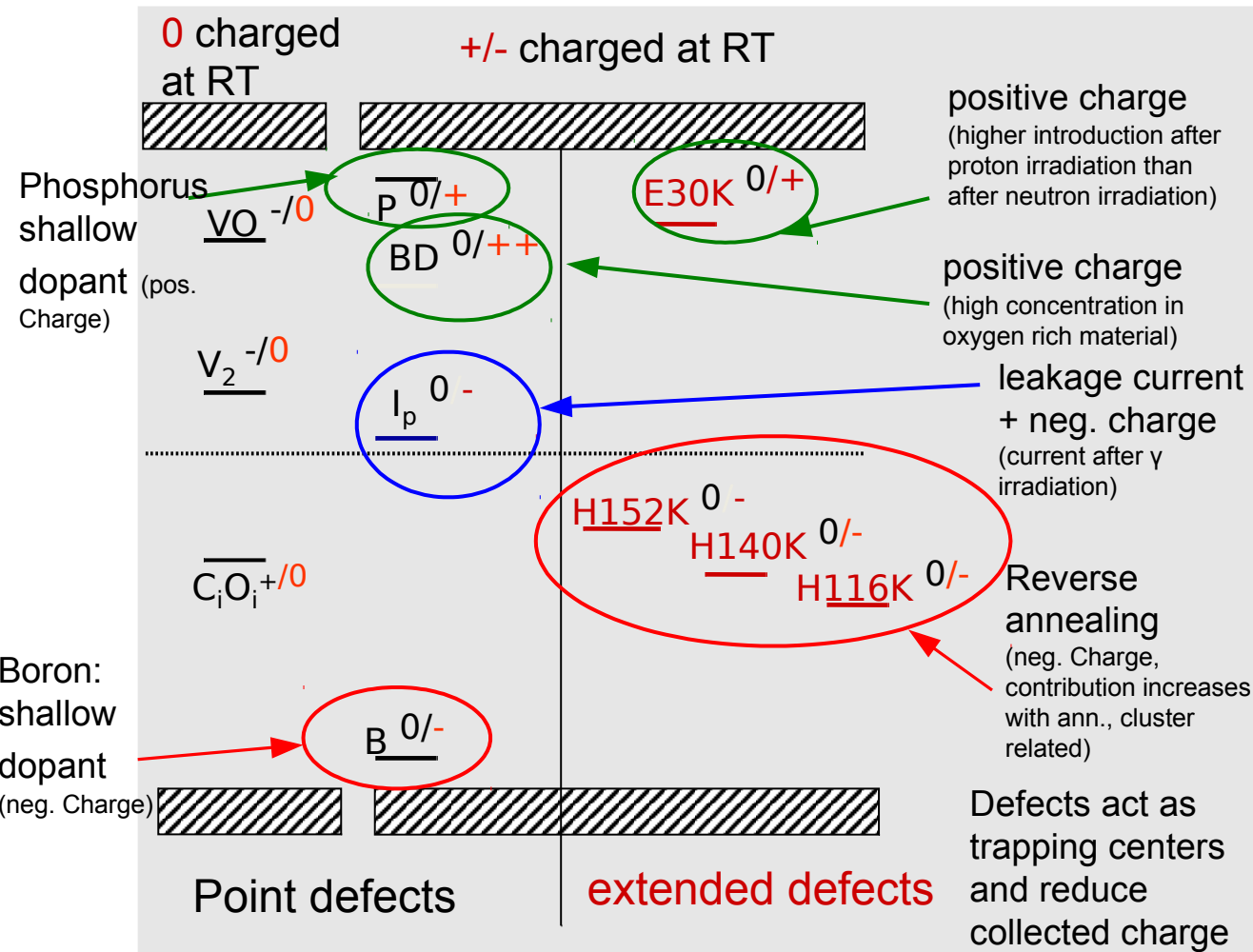
- Leakage current independent of material
  - Scales with fluence  $\alpha = 4.38 \times 10^{-17} A/cm^2$  up to  $2 \times 10^{15} Neq/cm^2$

- Leakage current decreases after annealing, temperature dependent
- DLTS result due to defects E4/E5 and E205a

# Defect Characterization Overview

Albert-Ludwigs-Universität Freiburg

- WODEAN (Workshop on Defect Analysis in Silicon Detectors) since 2005



## Achievements:

- Consistent set of defects after different irradiations
- Defect introduction rates depend on particle type and energy
- H152K indicated to trigger trapping

→ More measurements and understand effects by using simulation

G. Casse, M.Moll, LHCC report 2012

I.Pintilie et al., Appl. Phys. Lett.92 02410, 2008



# Simulation group in RD50

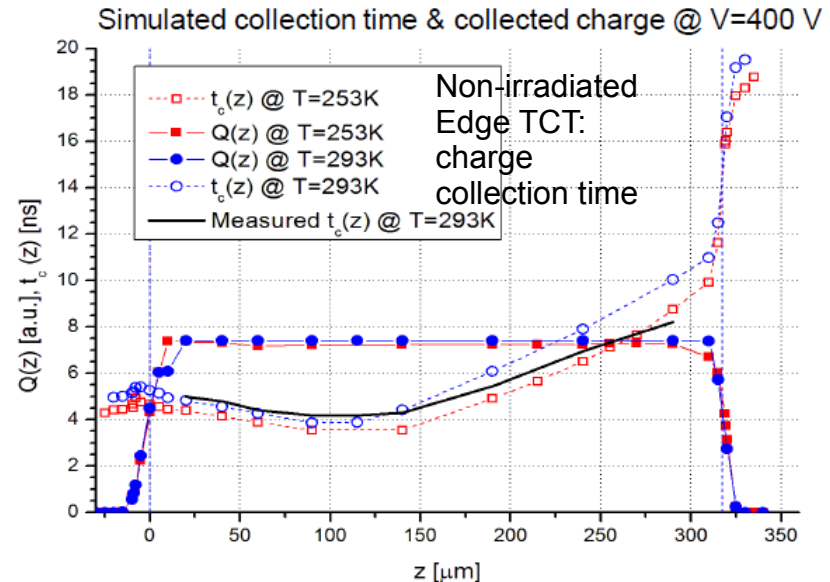
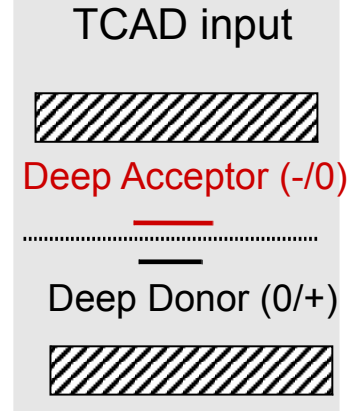
Albert-Ludwigs-Universität Freiburg

- **Goal: development of approach for simulation of performance of irradiated silicon detectors using professional software**

- Simulations needed to predict electric fields (double junction), trapping
- Several institutes involved
- Using effective mid gap levels in simulation
- Large parameter space needs tuning to experimental TCT results (introduction rates, cross sections of defects)

- **Start to have predictive power**
- **Leakage current, depletion voltage, partially trapping of irradiated sensor can be modelled**

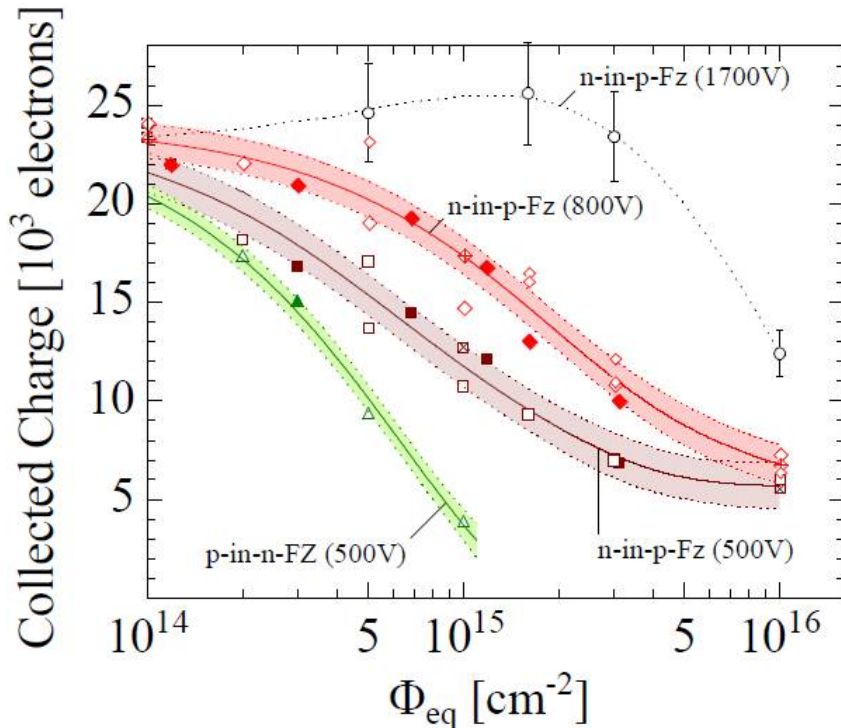
- Aim to prepare **common database** with cross sections, concentrations
- **More tuning** needed and ongoing e.g.using Edge-TCT results to compare E-field profile



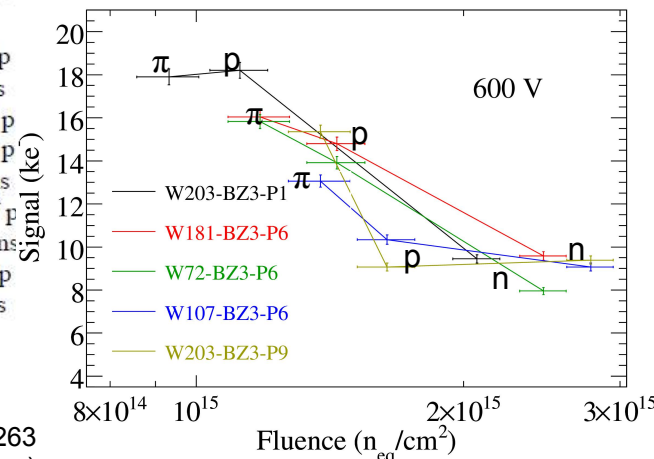
P-in-n, 320  $\mu\text{m}$ , strip  $w=14 \mu\text{m}$ , implant  $w=10 \mu\text{m}$ , pitch=80  $\mu\text{m}$  T. Peltola, 23<sup>rd</sup> RD50 Workshop Nov. 2013

See Poster: Development of Radiation Damage Model using TCAD tools for Irradiated Silicon Sensors

Task: Systematic evaluation of strip and pixel sensors connected to fast electronics before and after irradiation with protons, neutrons, pions



N-in-p FZ after pion, proton and neutron irradiation, beta source tests

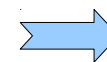


S. Kuehn, 21<sup>st</sup> RD50 Workshop Nov. 2012

After  $2.8 \cdot 10^{15}$  neq/cm<sup>2</sup>:  
 Collected charge 600 V  $9.0 \pm 0.7$  ke  
 Signal-to-noise ratio  $12.3 \pm 0.1$

→ n-in-p performs best:

- No space charge inversion
- Favourable combination of weighting and electric field after irradiation
- Readout at n-type electrodes: collection of electrons (fast), shorter trapping times, enhance amount of charge



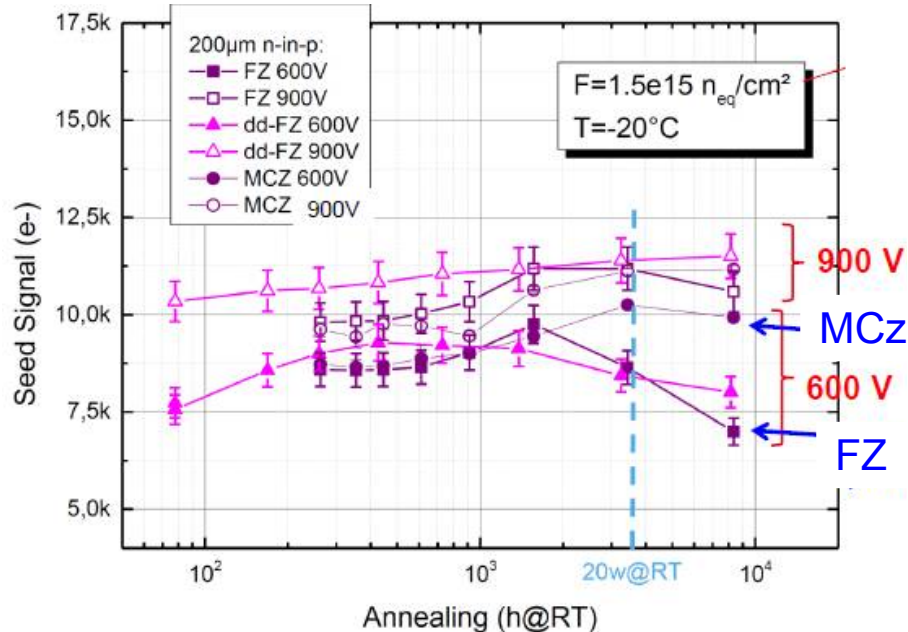
Baseline for upgrade of ATLAS and CMS silicon strip tracking detectors  
 (in current detectors p-in-n)

# Full detector systems: FZ vs. MCz and Thin detectors

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MCz with [O]  $\sim 5 \cdot 10^{17} \text{ cm}^{-3}$  (introduced by RD50)

- Sensors 200  $\mu\text{m}$  thick,  $1.5 \cdot 10^{15} \text{ neq/cm}^2$  protons

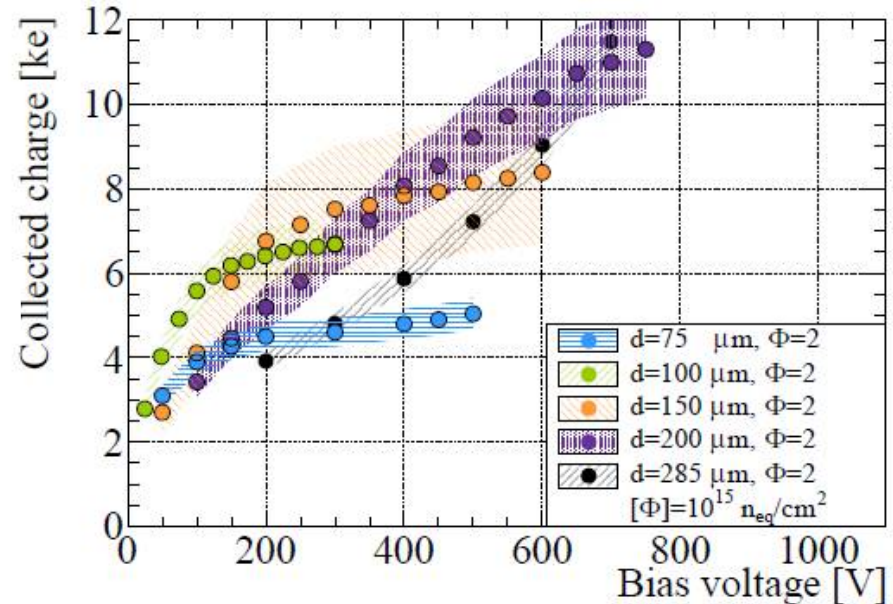


G. Steinbrück, 23<sup>rd</sup> RD50 Workshop Nov. 2013

- MCz performs better than FZ
- MCz less affected by annealing, stable annealing behaviour
- Improved performance in mixed fields due to compensation of neutron and charged particle damage in oxygen rich MCz

Thin detectors

- CIS FZ sensors of different thickness, ATLAS FEI4, 25 MeV protons, beta source



S. Terzo, 23<sup>rd</sup> RD50 Workshop Nov. 2013

- 100-150  $\mu\text{m}$  thick sensors show the highest collected charge at moderate voltages (200-300 V) for fluences above  $1 \cdot 10^{15} \text{ neq/cm}^2$
- Beam tests show 98.1% hit efficiency (100  $\mu\text{m}$  active edge sensor, 300V,  $5 \cdot 10^{15} \text{ neq/cm}^2$ )
- Less material

See also Talks of A. Macchiolo today and A. Junkes on Friday



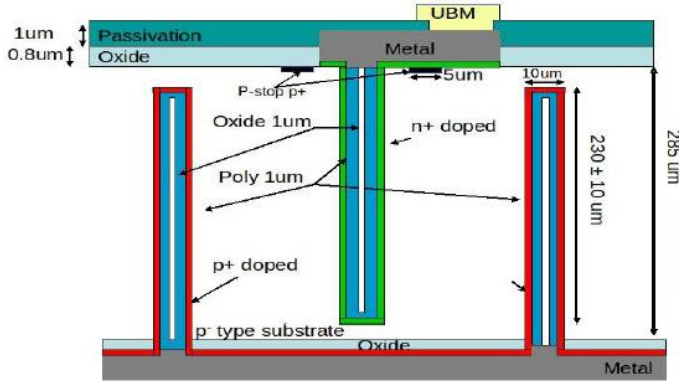
# New Structures: 3D sensors

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3D sensors: doped columns vertical to surface

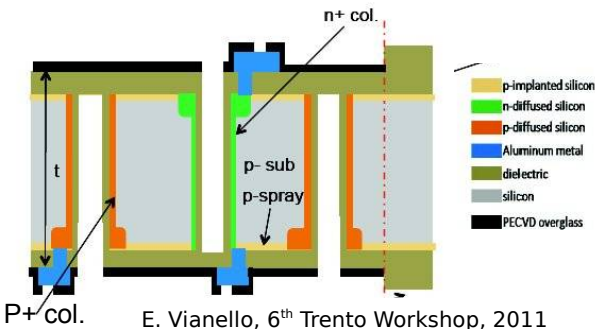
- Decoupling of depletion voltage and detector thickness (collected charge) but have low-field region

CNM: columns part. filled

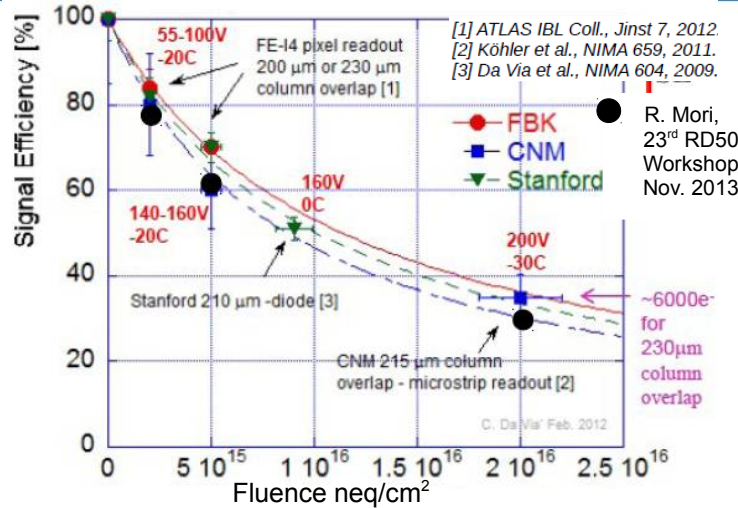


G. Pellegrini, NIM A 592 (2008) 38-43

FBK 3D double side double type sensor: columns through wafer, empty

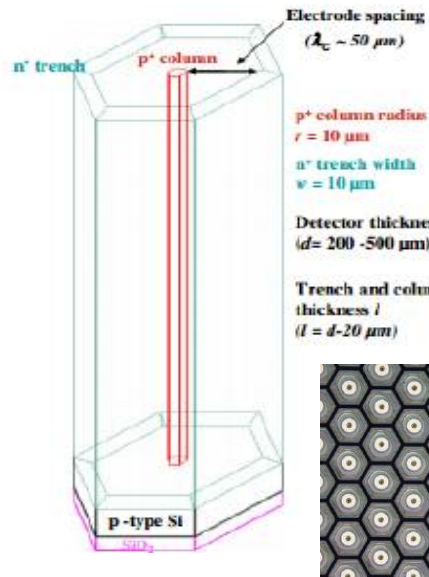


E. Vianello, 6<sup>th</sup> Trento Workshop, 2011



→ Well performing and installed in ATLAS IBL  
→ decent signal after  $2 \cdot 10^{16}$  neq/cm<sup>2</sup>

New development: 3D-Trench Electrode Detector (BNL&CNM)



- Overcomes low-field region in 3D detectors
- First sample  $V_{FD} \sim 95$  V after  $1 \cdot 10^{16}$  neq/cm<sup>2</sup>
- Uniform electric field
- Full charge collected by <sup>241</sup>Am source test

Next: position-resolved laser tests

# New Structures: Active/slim edge sensors

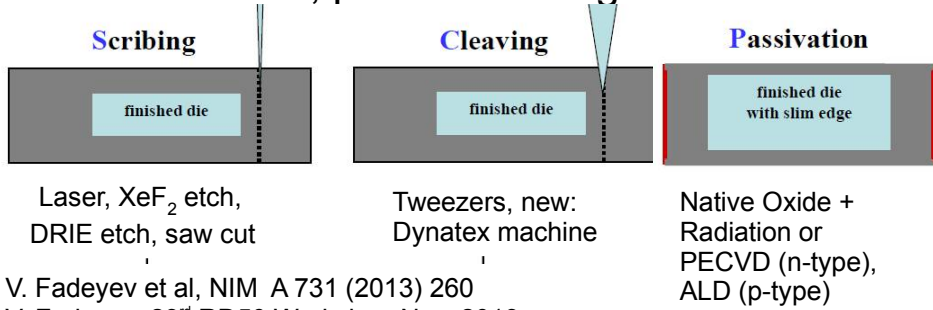


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## Minimize “dead” area of sensors: several techniques

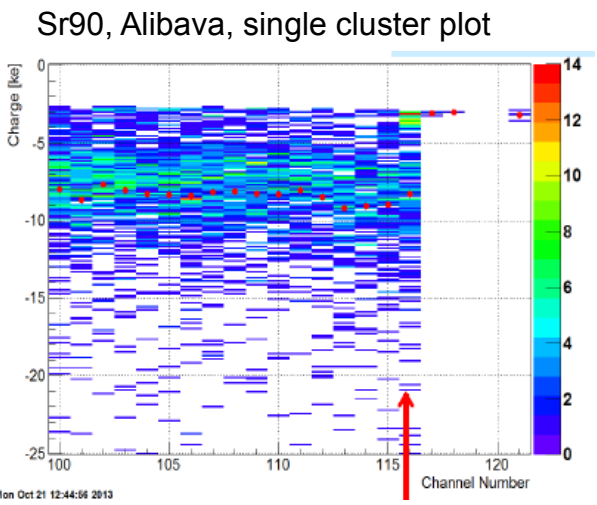
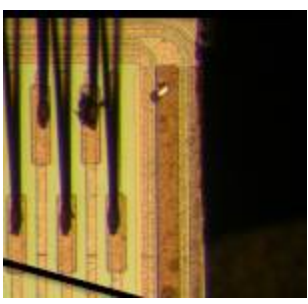
### SCP slim edges

- Exploits scribe and cleave technique on planar and 3D devices, passivated edge



V. Fadeyev et al, NIM A 731 (2013) 260  
V. Fadeyev, 23<sup>rd</sup> RD50 Workshop Nov. 2013

CIS n-in-p, 285 μm thick, 150 μm slim edge, 800 V bias, 4\*10<sup>15</sup> neq/cm<sup>2</sup>



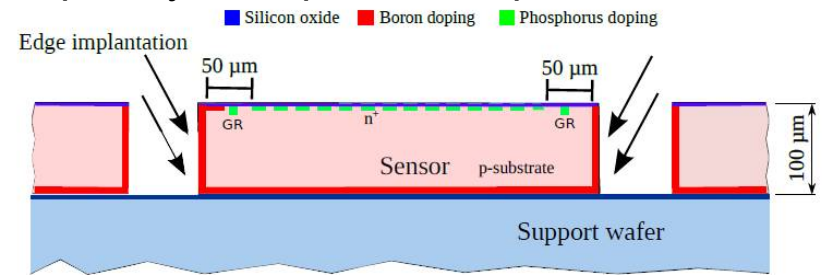
### Similar median charge as for other strips

Also under development at HPK

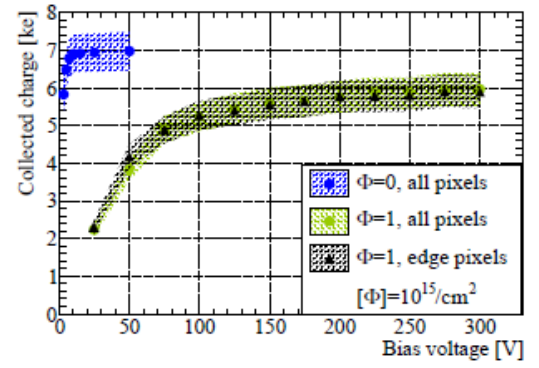
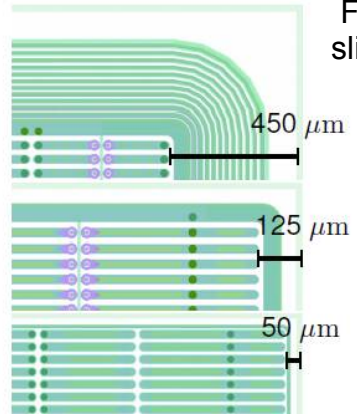
03.06.14

### VTT/MPI active edges project

- Pixel sensors with slim edges, trenches doped by four-quadrant implantation



FE-13 FZ silicon, 100 μm thick, 125 μm slim edge, threshold: 1500 e<sup>-</sup>



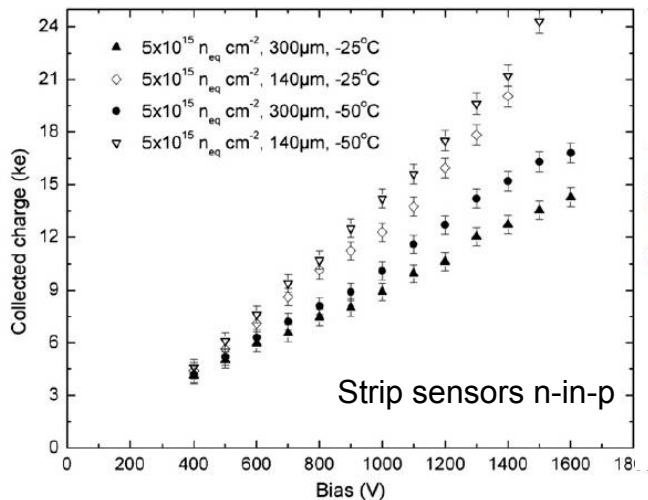
Hit efficiency (98.9±3)% at 300 V after 5\*10<sup>15</sup> neq/cm<sup>2</sup>

S. Terzo, 23<sup>rd</sup> RD50 Workshop Nov. 2013

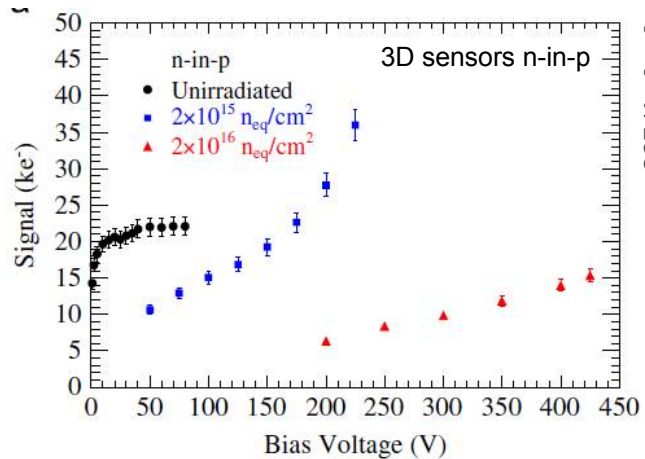
Overall efficiency, I<sub>leak</sub> and noise unaffected by edge-cutting

# Full detector systems: Charge Multiplication

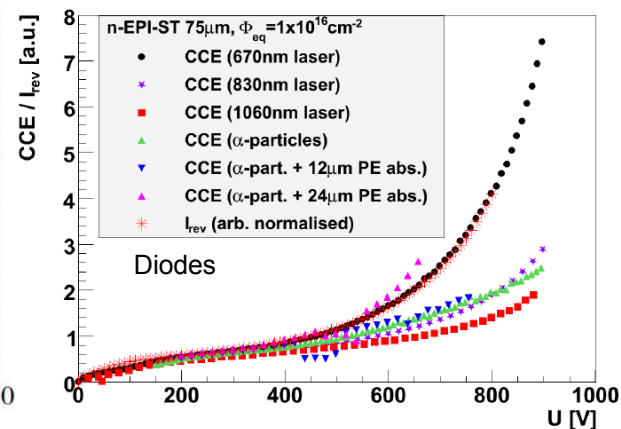
**Charge multiplication observed after irradiation to  $2\text{-}5 \times 10^{15}$  neq/cm<sup>2</sup>**  
 Characterized with different techniques and in different type of devices



G. Casse, NIM A, 624(2011), 401–404



M. Köhler, NIM A, 659 (2011), 272–281,  
 16<sup>th</sup> RD50 Workshop, June 2010



J. Lange, 16<sup>th</sup> RD50 Workshop, June 2010

Charge Collection (Beta source, Alibava readout)

**Origin:** Irradiation leads to high negative space charge concentration in detector bulk  
 → increase of the electric field close to n-type strips  
 → impact ionization

**Goals:**

- Simulation and prediction of charge multiplication
- Long term, S/N behaviour
- Is exploitation of charge multiplication possible?

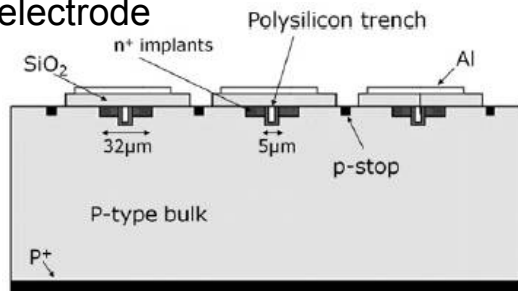
- Dedicated R&D in RD50 to understand and optimize multiplication mechanism
- Evaluating possibility to produce fast segmented sensors



# Full detector systems: Enhancing Charge Multiplication

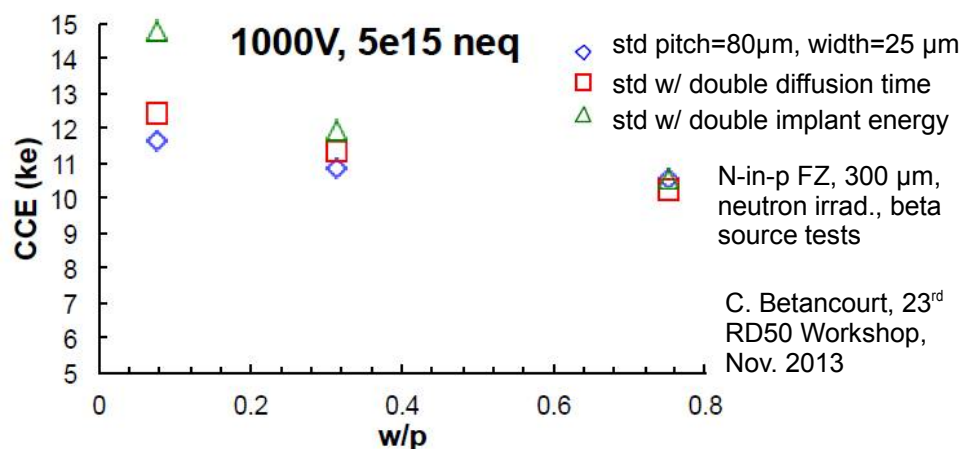
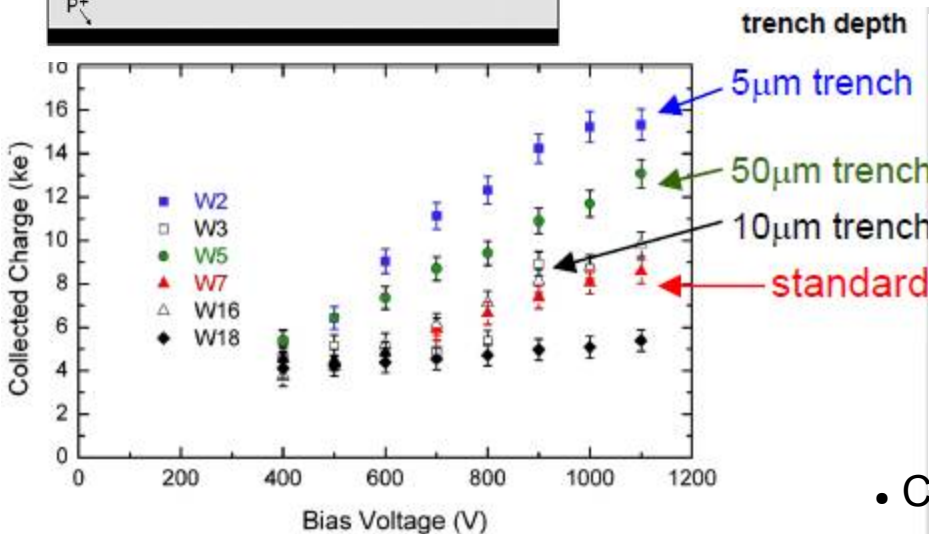
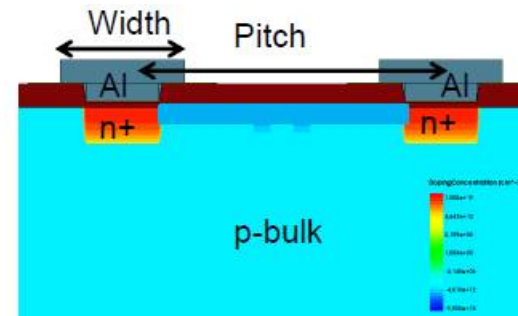
## Production of sensors with trenches:

- 5, 10, 50  $\mu\text{m}$  deep, 5  $\mu\text{m}$  wide in center on n+ electrode



G. Casse, NIM A 669 (2013) 9-13,  
P. Fernández-Martínez, NIM A 658 (2011) 98-102

## N-in-p sensors with different strip widths and pitches:



C. Betancourt, 23<sup>rd</sup> RD50 Workshop, Nov. 2013

After  $5 \cdot 10^{15}$  neq/cm<sup>2</sup> neutrons, n-in-p sensor 300  $\mu\text{m}$  thick  
→ CCE higher for sensors 5 and 50  $\mu\text{m}$  trenches compared to standard sensors

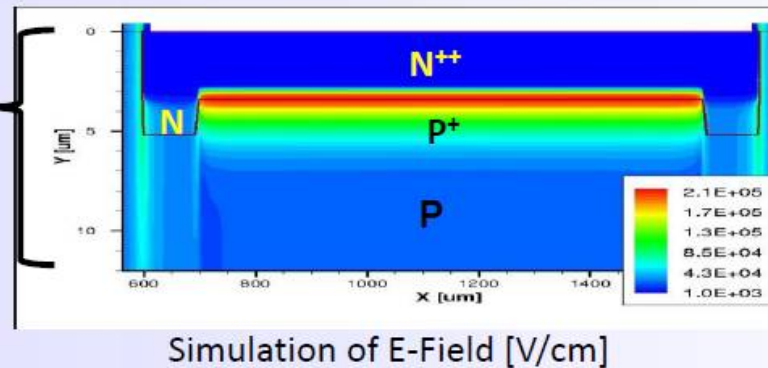
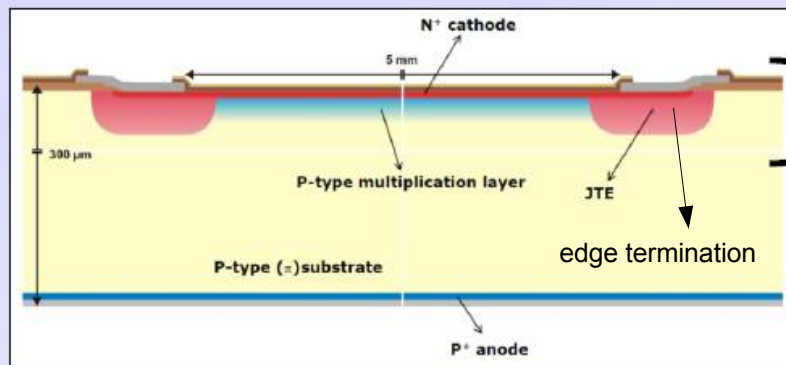
- Charge multiplication seen after  $V_{\text{Bias}} > 600$  V
- Both Extr. Diff. and 2E imp. show signs of CM with respect to standard wafer
- Lower w/p ratio leads to more pronounced multiplication
- Long term behaviour under test, first indications for degradation after few days

see also talk of R. Klanner on Friday

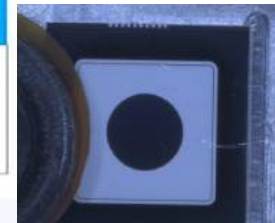
# New Structures: Low Gain Avalanche Diodes - LGAD

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Diodes with implemented multiplication layer (deep p+ implant):  $n^{++}-p^+-p-p^+$

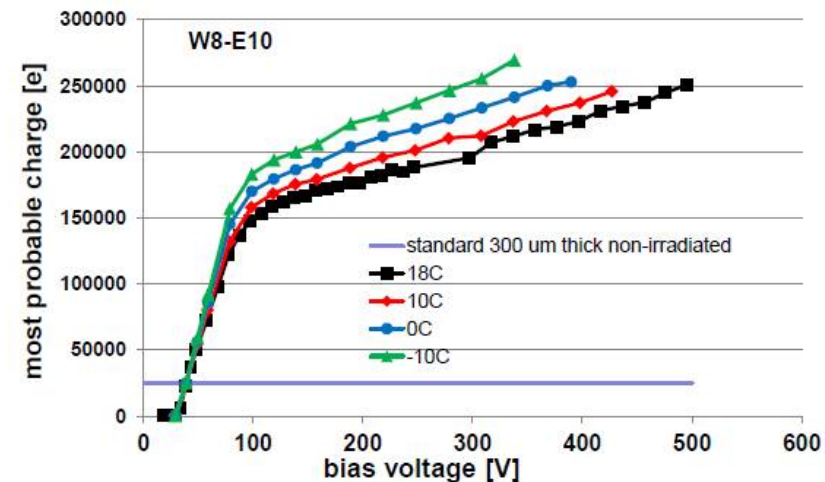
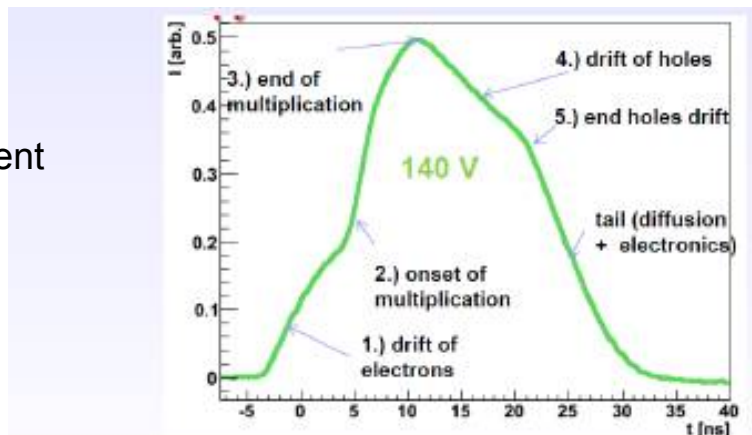


M. Baselga, 8<sup>th</sup> Trento Workshop, 2013



- P-doped diffusion under cathode → multiplication layer
- Edge termination needed: low doping n-well
- First samples under test
- Gain of ~10 before irradiation (Landau spectra Sr90)
  - Current and noise independent of gain

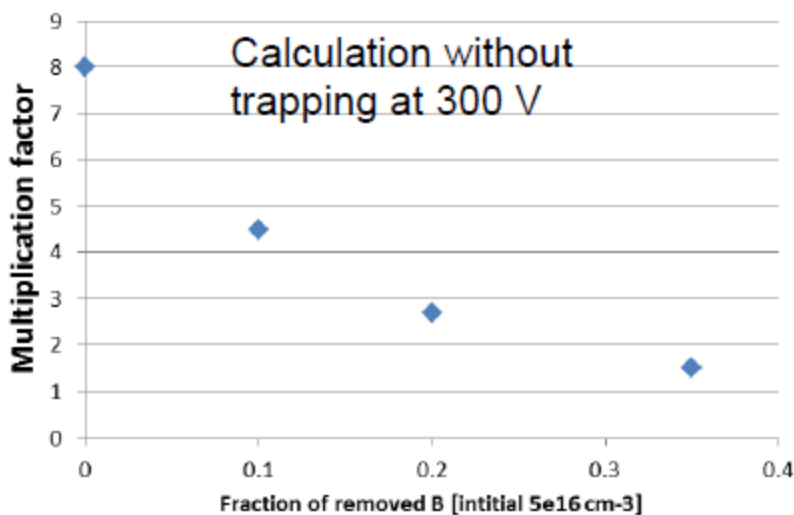
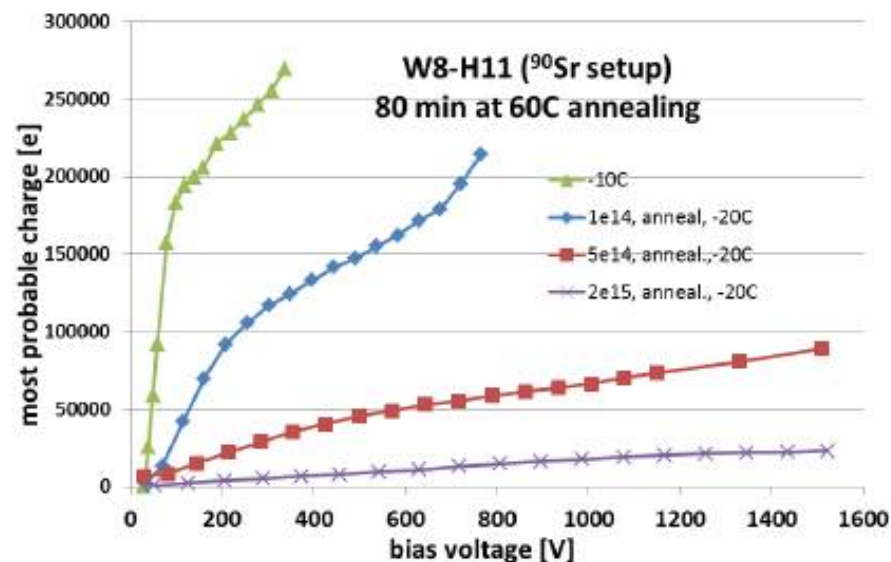
TCT measurement matches simulation



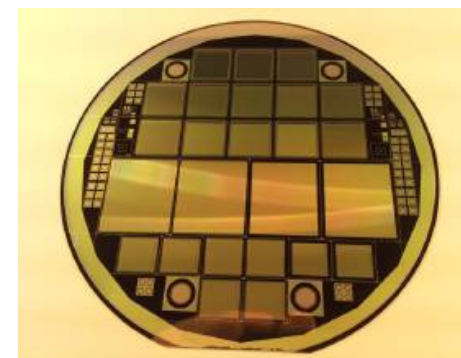
G. Kramberger, 22<sup>nd</sup> RD50 workshop, June 2013

# New Structures: Low Gain Avalanche Detectors – LGAD irradiated

- After irradiation: Degradation in multiplication, gain reduces to about 1.5
- Reasons (under investigation):
  - Boron removal in p-type layer, not due to electron trapping
  - Reduction in electric field  
→ Removal of initial acceptors, more removal than in normal diodes
  - Noise scales with multiplication
  - 6000 e<sup>-</sup> after  $1 \cdot 10^{16}$  neq/cm<sup>2</sup>
- Gain depending on temperature (high T, low gain)



- More wafers for detailed tests in production
- Irradiation programme with protons, gammas and neutrons



# Achievements of RD50 in light of LHC experiments



- Observed radiation damage in LHC experiments agrees with predictions developed by RD50
  - Leakage current increase in ATLAS, depletion voltage evolution in LHCb
- Recommendations for silicon tracking detectors at HL-LHC
  - Inner layers with fluences of about  $1 \cdot 10^{16}$  neq/cm<sup>2</sup>
    - planar sensors collect decent amount of charge, hit efficiency 97%
    - n-in-p (or n-in-n) candidate material (important collection of electrons)
    - thin detectors overcome problem of requirement of high bias voltage, advantageous with doses  $> 1 \cdot 10^{15}$  neq/cm<sup>2</sup>
    - 3D detectors are alternative option and show good performance with lower bias voltage (used now in IBL of ATLAS experiment)
  - Outer layer with fluences of about  $2 \cdot 10^{15}$  neq/cm<sup>2</sup>
    - planar FZ n-in-p sensors baseline for ATLAS and CMS upgrade strip tracker (FZ has reverse annealing after  $> 12$  weeks at room temperature)
    - MCz also option, damage is compensated in mixed fluences, long-term beneficial annealing (50 weeks at room temperature)

- Recommendations for silicon tracking detectors at HL-LHC
- Progress in understanding microscopic defects, origin of positive space charge
- Simulation working group: simulations get predictive power, common database in preparation
- New structures under investigation: 3D-Trench detectors, thin detectors
- Consolidation of data on n-in-p-type, thin segmented and slim/active edge sensors
- Charge multiplication investigated systematically to allow its exploitation  
→ Dedicated sensor productions: Trenches, Pitch/Width, Low Gain Avalanche Diodes

- RD50 collaboration works on radiation hard semiconductor devices for LHC experiments
  - Tested plenty of different devices (material, geometry, engineering)
  - Significantly improved understanding of radiation effects
  - Developed rich tooling for sensor characterization: Alibava, Edge-TCT, Beam telescope
  - Common sensor production
  - Inter-experiment working towards advise for selection for tracking detectors at HL-LHC and beyond: “LHC-wide” exchange of knowledge
- Other projects:
  - Low-resistance strip sensor project
  - Annealing parametrisation, carrier de-trapping
  - Irradiation to extreme fluences

**Very active community and many projects ongoing!**  
**More on [www.cern.ch/rd50](http://www.cern.ch/rd50)**  
**Thank you to all colleagues for material!**



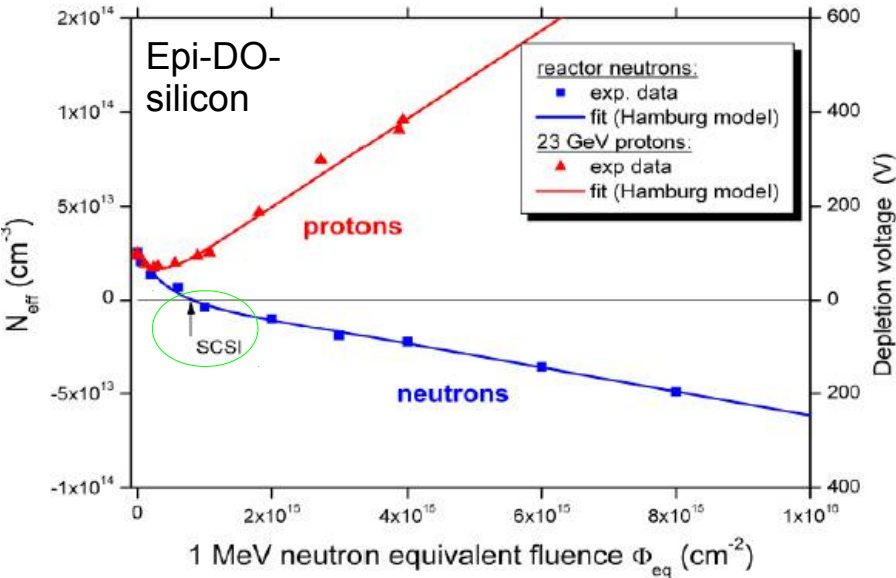


# Impact of Defects: Change of $N_{\text{eff}}$

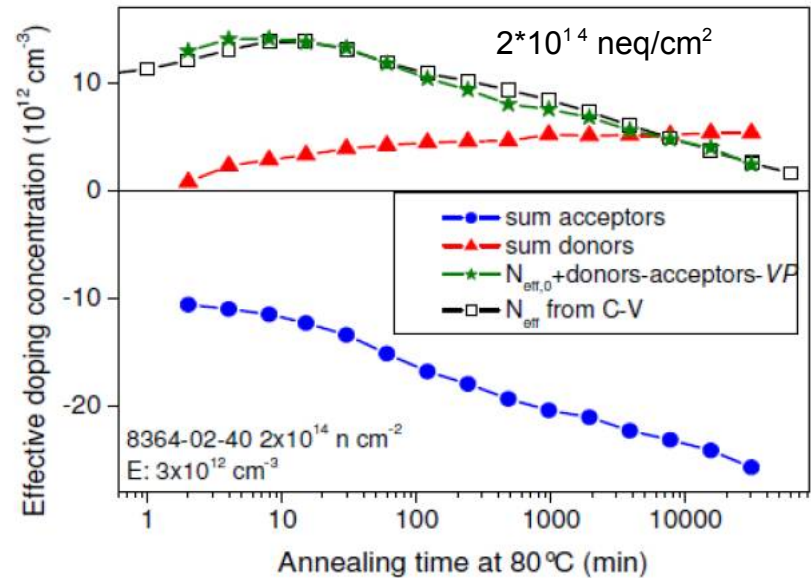
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- Dependence on particle type: proton vs. neutron irradiation

- Effect of reverse annealing after irradiation



I. Pintilie et al., NIM A 611 (2009) 52-68



A. Junkes PoS(Vertex2011)035, I. Pintilie et al., APL 92,024101 (2008)

- TSC result:
  - Donor **E(30K)** introduces positive space charge after proton irradiation  
Violates NIEL hypothesis!
  - Introduces more positive space charge in oxygen rich material

- TSC result:
  - Acceptors **H(116K), H(140K), H(152K)** increase with reverse annealing
  - H(116K) might depend on oxygen concentration  
→ increase of negative space charge

# Defect Characterization



Defects induced by irradiations in Si (forming and transforming at ambient temperatures)

Defects	$\sigma_{a,p}$ [cm <sup>2</sup> ]	E <sub>A</sub> [eV]	Assignment/References	Impact on electrical characteristics at RT
E(30K)	$\sigma_n = 2.3 \times 10^{-14}$	E <sub>C</sub> - 0.1	Electron trap with a donor level in the upper half of the Si bandgap / [Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52]	On the N <sub>eff</sub> by introducing positive space charge -It makes the difference between proton and neutron irradiations -More generated in O rich material
BD <sub>A</sub> <sup>0++</sup> BD <sub>B</sub> <sup>0++</sup>	$\sigma_n = 2.3 \times 10^{-14}$ $\sigma_n = 2.7 \times 10^{-12}$	E <sub>C</sub> - 0.225 E <sub>C</sub> - 0.15	Bistable Thermal double donor <b>TDD2</b> (two configurations A and/or B) - Electron trap with a donor level in the upper half of the Si bandgap/ [Appl. Phys. Lett. 50 (21) (1987) 1500; Nucl. Instr. and Meth. in Phys. Res. A 514 (2003) 18; Nucl. Instr. and Meth. in Phys. Res. A 556 (2006) 197; Nucl. Instr. and Meth. in Phys. Res. A 583 (2007) 58]	On the N <sub>eff</sub> by introducing positive space charge -Strongly generated in O rich material
I <sub>p</sub> <sup>+0</sup>  I <sub>n</sub> <sup>0-</sup>	$\sigma_p = (0.5-9) \times 10^{-15}$  $\sigma_n = 1.7 \times 10^{-15}$ $\sigma_n = 9 \times 10^{-14}$	E <sub>V</sub> + 0.23  E <sub>C</sub> - 0.55	Donor level of V <sub>2</sub> O or of a still unknown C related defect / [Appl. Phys. Lett. 81 (2002) 165; Appl. Phys. Lett. 83, 3216 (2003); Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52] Acceptor level of V <sub>2</sub> O or of a still unknown C related defect/[Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52, Appl. Phys. Lett. 81 (2002) 165]	On the N <sub>eff</sub> by introducing negative space charge and on LC -Strongly generated in O lean material
E <sub>4</sub> E <sub>5</sub>	$\sigma_n = 1 \times 10^{-15}$ $\sigma_n = 7.8 \times 10^{-15}$	E <sub>C</sub> - 0.38 E <sub>C</sub> - 0.46	Acceptor in the upper part of the gap associated with the double charged and single charged states of V <sub>3</sub> , respectively (V <sub>3</sub> <sup>2-</sup> and V <sub>3</sub> <sup>-0</sup> ) / [J. Appl. Phys. 111 (2012) 023715.]	On LC
H(116K)	$\sigma_p = 4 \times 10^{-14}$	E <sub>V</sub> + 0.33	Hole trap with an acceptor level in the lower part of the Si bandgap - Extended defect (cluster of vacancies and/or interstitials) / [Appl. Phys. Lett. 92 (2008) 024101, Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52-68]	On the N <sub>eff</sub> by introducing negative space charge
H(140K)	$\sigma_p = 2.5 \times 10^{-15}$	E <sub>V</sub> + 0.36	Hole trap with an acceptor level in the lower part of the Si bandgap - Extended defects (clusters of vacancies and/or interstitials)/ [Appl. Phys. Lett. 92 (2008) 024101, Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52-68]	On the N <sub>eff</sub> by introducing negative space charge
H(152K)	$\sigma_p = 2.3 \times 10^{-14}$	E <sub>V</sub> + 0.42	Hole trap with an acceptor level in the lower part of the Si bandgap - Extended defects (clusters of vacancies and/or interstitials)/ [Appl. Phys. Lett. 92 (2008) 024101, Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52-68]	On the N <sub>eff</sub> by introducing negative space charge
VO <sub>1</sub> <sup>-0</sup>	$\sigma_n = 1.44 \times 10^{-14}$	E <sub>C</sub> - 0.176	VO <sub>1</sub> <sup>-0</sup> / [J. Appl. Phys. 79(1996)3906; Mat. Sci. in Semic. Proc. 3 (2000) 227]	
C <sub>1</sub> C <sub>2</sub> <sup>-0</sup>	$\sigma_n = 1.4 \times 10^{-14}$	E <sub>C</sub> - 0.171	C <sub>1</sub> C <sub>2</sub> <sup>-0</sup> / [Phys. Rev. Lett. 60 (1988) 460-463, Phys. Rev. B42 (1990) 5765]	
H(40K)	$\sigma_p = 1.7 \times 10^{-15}$	E <sub>V</sub> + 0.09	Hole trap/ [Nucl. Instr. and Meth. in Phys. Res. A 611 (2009) 52-68]	
C <sub>1</sub> <sup>+0</sup>	$\sigma_p = 4.3 \times 10^{-15}$	E <sub>V</sub> + 0.284	C <sub>1</sub> <sup>+0</sup> / [M. Moll, PhD Thesis, University of Hamburg, DESY-THESIS-1999-040, 1999]	
C <sub>1</sub> O <sub>1</sub> <sup>+0</sup>	$\sigma_p = 4.3 \times 10^{-15}$		[J. Appl. Phys. 79(1996)3906]	
V <sub>2</sub> <sup>-0</sup>	$\sigma_n = 2.1 \times 10^{-15}$	E <sub>C</sub> - 0.424	V <sub>2</sub> <sup>-0</sup> / [J. Appl. Phys. 79(1996)3906; M. Moll, PhD Thesis, DESY-THESIS-1999-040, 1999]	
H(87K)	$\sigma_p = 0.3 \times 10^{-15}$	E <sub>V</sub> + 0.193	V <sub>3</sub> <sup>0+</sup> / [Phys. Status Solidi A 208 (2011) 568.]	

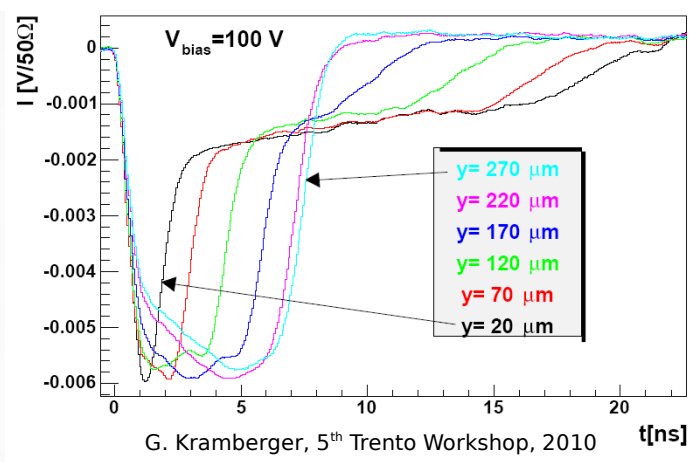
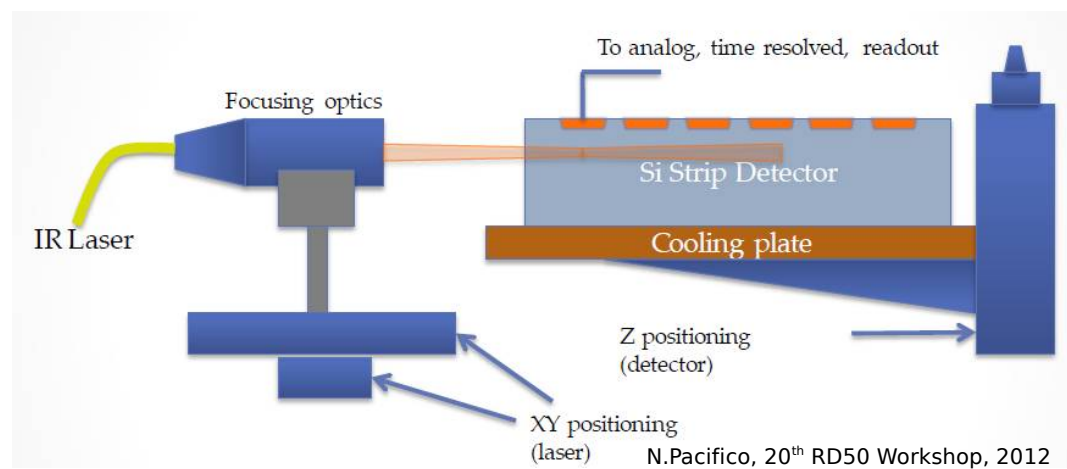
I. Pintilie/ R. Radu, 23rd RD50 Workshop, Nov. 2013

# Detector Characterization: Investigation of Electric Fields with Edge-TCT



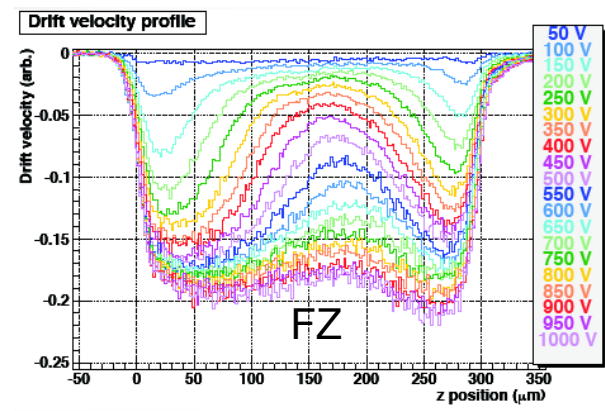
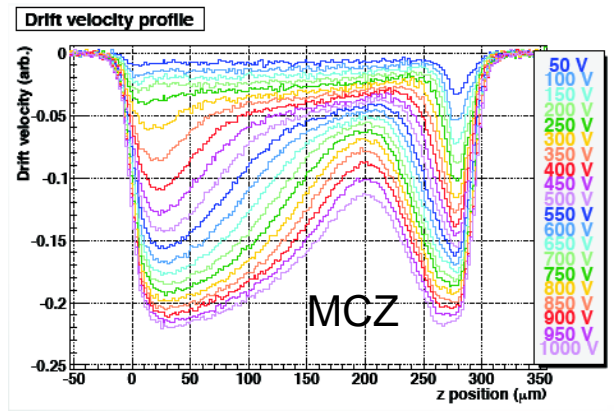
- Goal: Measurement of electric field in unirradiated and irradiated devices, usual TCT (Transient Charge Technique) not working due to trapping after irradiation

Edge-TCT, G. Kramberger, IEEE TNS, VOL. 57, NO. 4, AUGUST 2010, 2294



- Example: n-on-p strip detector (pitch 80 μm), irradiated to  $1 \cdot 10^{16}$  neq/cm<sup>2</sup>, with protons, no annealing

N. Pacifico, 20<sup>th</sup> RD50 Workshop, 2012



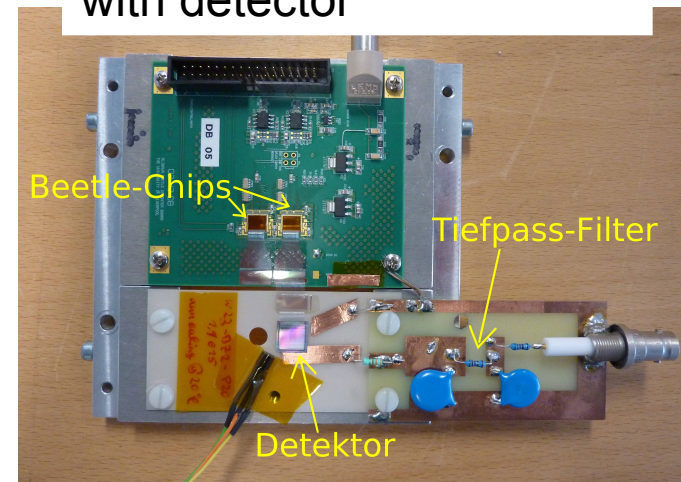
$I(y, t \sim 0)$  proport.  $v_e + v_h$   
 Different drift velocity in FZ and MCZ silicon



Systematic evaluation of strip and pixel sensors connected to fast electronics before and after irradiation with protons, neutrons, pions

- Use fast (40 MHz) analogue or binary readout electronics
- Determine parameters like collected charge, noise, signal-to-noise by using beta source set-ups, laser set-ups and test beams
- Design and realization of pixel/strip detectors in contact with manufacturers  
(CiS, CNM, HIP, HPK, Micron, Sintef)

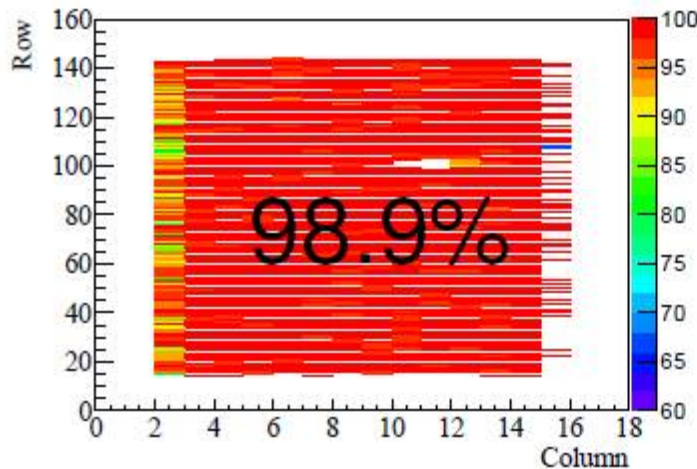
ALIBAVA daughter board with detector



- RD50 test beam setup (additional to other setups in the Collaboration (EUDET, CMS))
  - Based on ALIBAVA system with analogue fast readout
  - Device under test and sensors for track reconstruction run with same readout
  - Allows easy handling and high resolution measurements

## Hit efficiency: VTT 100 $\mu\text{m}$ FE-I3

- ▶ PPS test beam at DESY
  - ▶ 4 GeV electrons
  - ▶ EUDET telescope
  - ▶ perpendicular incidence tracks



### ▶ VTT 100 $\mu\text{m}$ FE-I3 Float Zone

- ▶ 125  $\mu\text{m}$  slim edge
- ▶ threshold: 1600  $e^-$
- ▶ 20 ToT at 60 ke
- ▶  $\Phi = 5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- ▶  $(98.9 \pm 0.3)\%$  global hit efficiency at 300 V



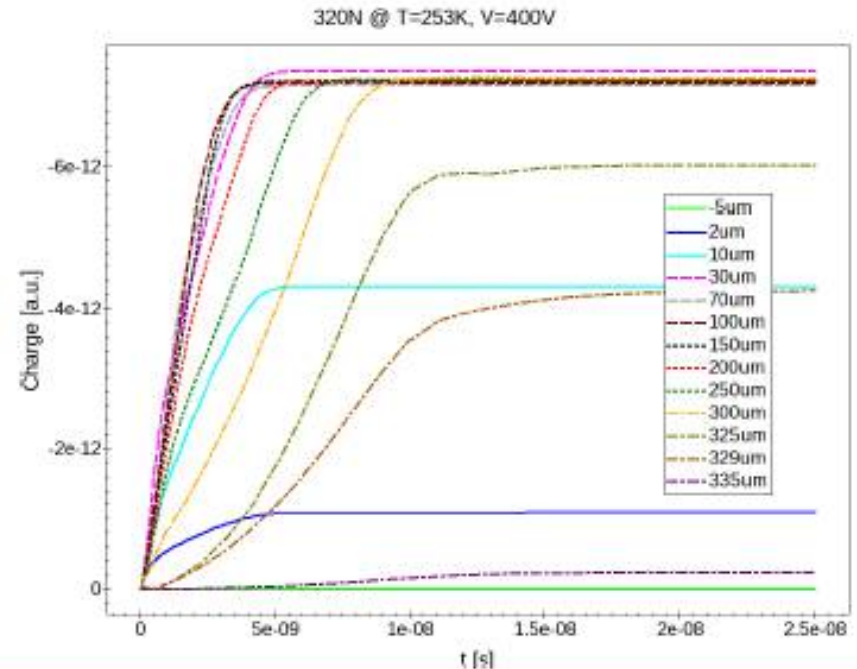
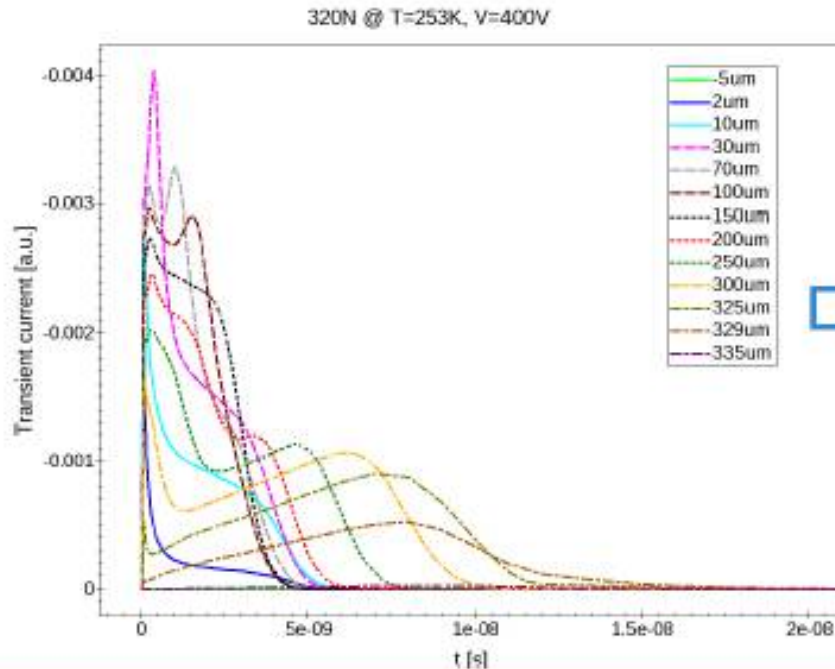
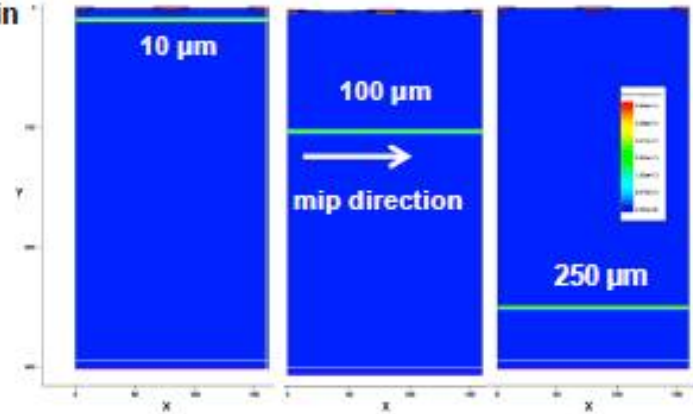


# Edge-TCT: Lifetime of charges

Albert-Ludwigs-Universität Freiburg

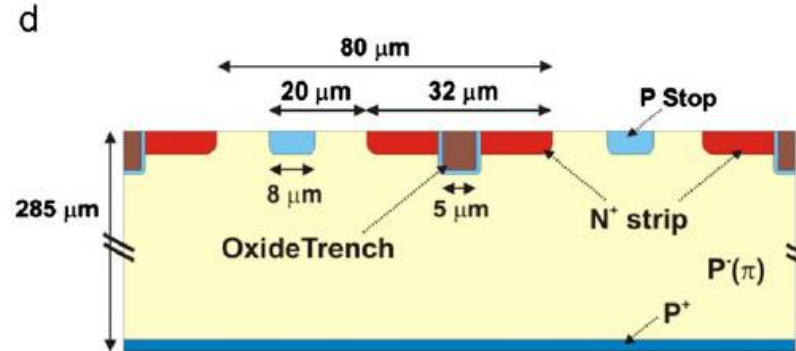
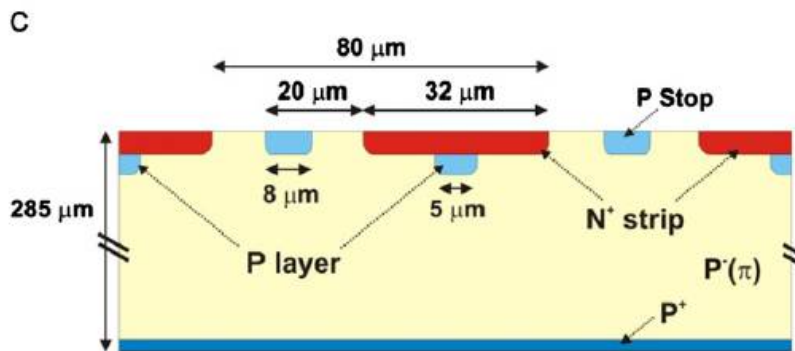
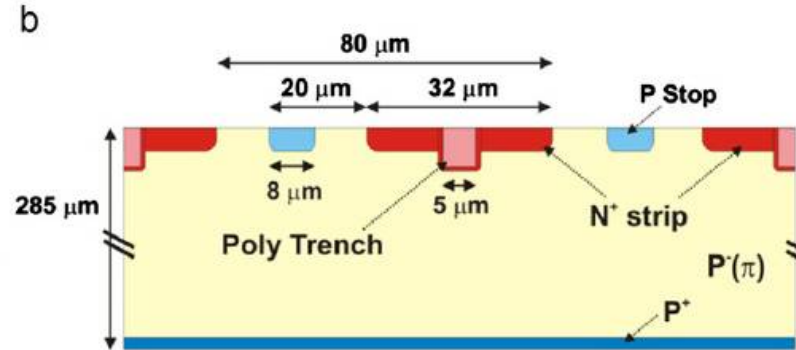
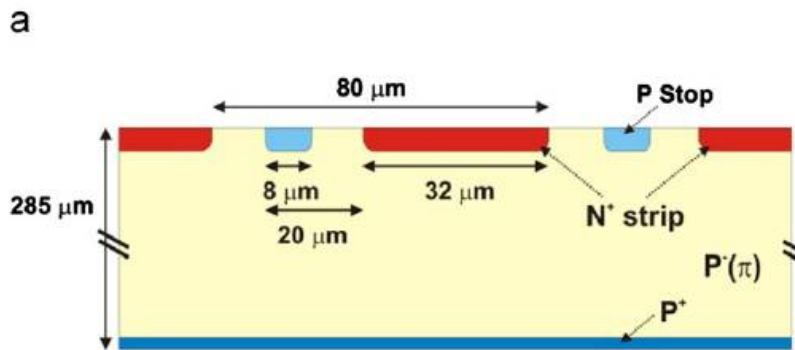
- **Goal:** extract electric field  $E$  from drift velocity  $v_{\text{drift}}$  using eTCT
- eTCT provides measurement of collection time  $t_c$  that is proportional to the  $v_{\text{drift}}$
- $v_{\text{drift}}$  is related to the  $E \rightarrow$  possible to determine  $E$  out of drift velocity?
  
- Collected eTCT generated transient signals and charges as a function of injection distance:

MIP trajectories in 300N device:



T. Peltola, 23rd RD50 Workshop Nov. 2013

**a** standard, **b** poly trench including poly silicon doped with phosphorus, **c** p-layer with p-type diffusion, **d** oxide trench

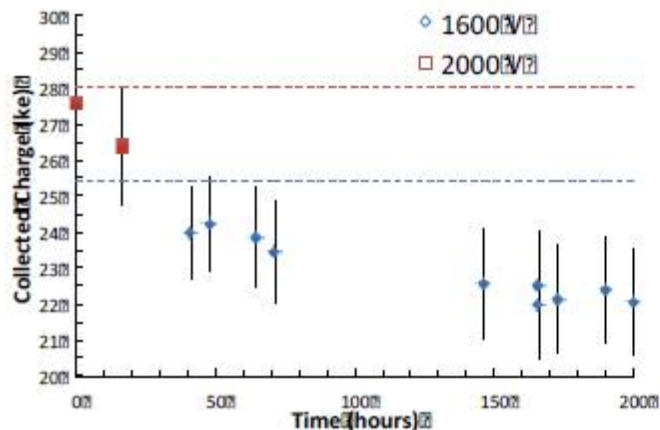


P. Fernández-Martínez, NIM A 658 (2011) 98-102

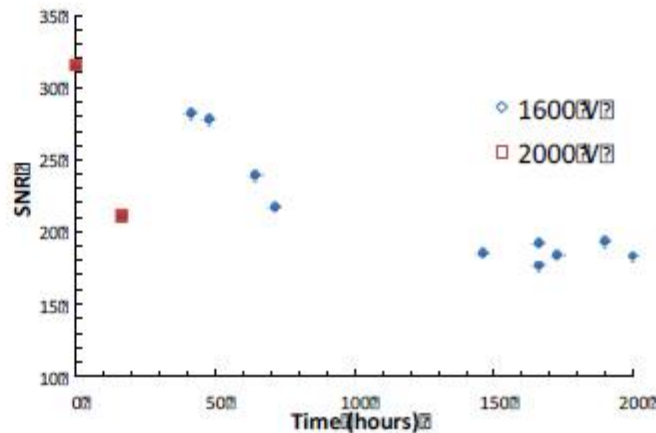
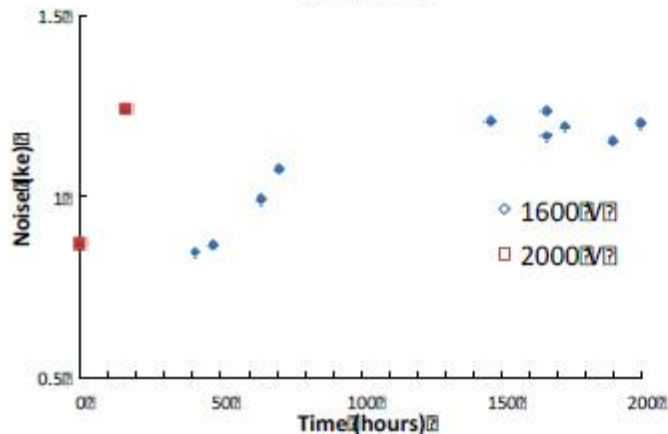
# Full detector systems: Enhancing Charge Multiplication

Long term behaviour of charge multiplication:

## Long-term tests (std, p80, w60, 1e15)



- Real-world application requires sensors to be operated at high voltages for long time intervals
- Initial tests taken over many days indicates degradation of the CM effect
- While signal goes down with time, noise increases

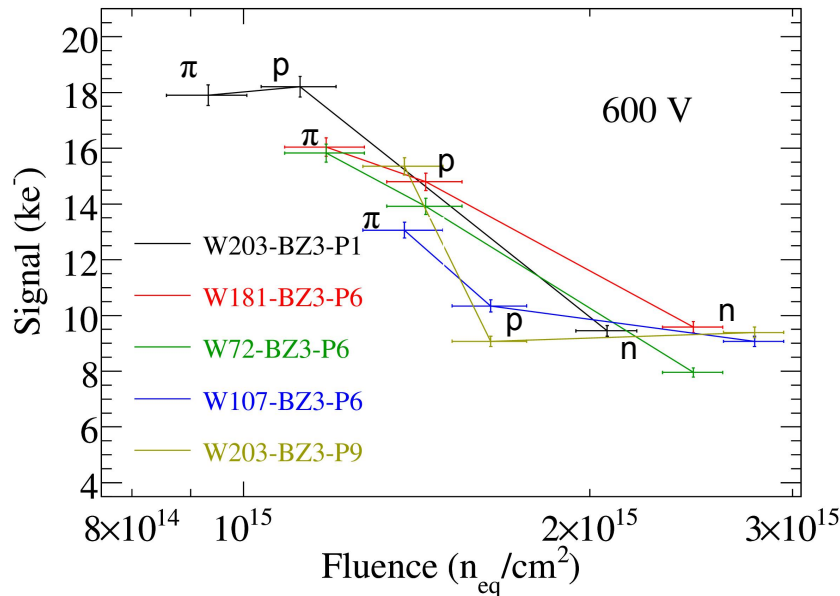


November 13, 2013

C. Betancourt, 23rd RD50 Workshop, CERN

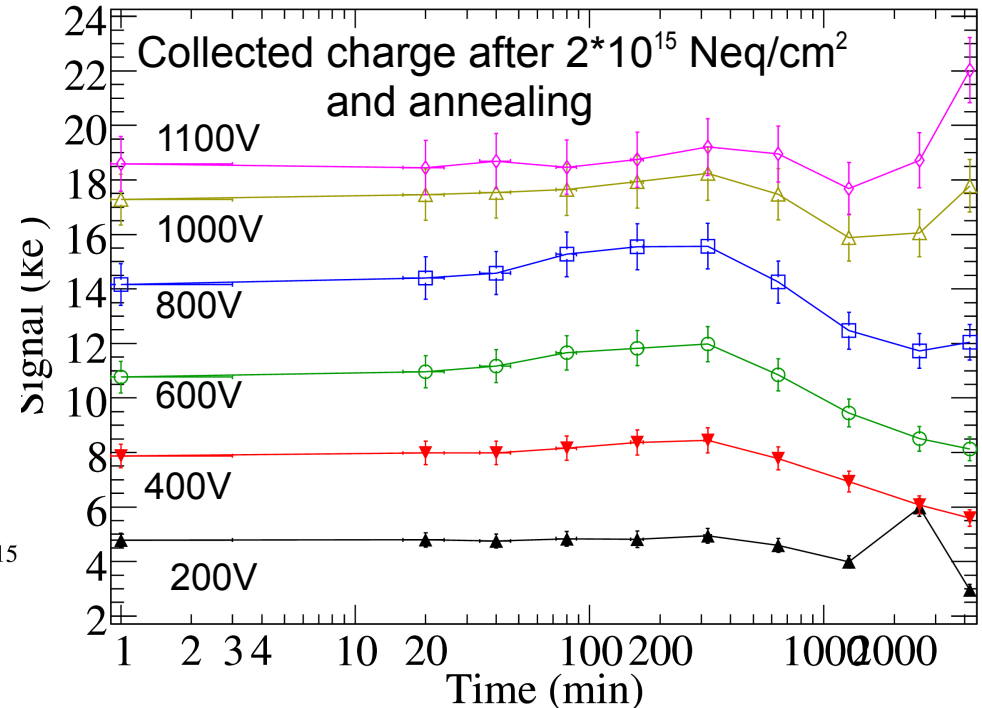
14

Example: FZ n-in-p ministrip sensors (HPK 300  $\mu\text{m}$  thick, 80  $\mu\text{m}$  pitch), tested with beta source, readout with ALIBAVA system (40 MHz) and irradiated with pions, protons and neutrons



S. Kuehn, 21<sup>st</sup> RD50 Workshop Nov. 2012

- Collected charge reduces at 600 V to  $9.0 \pm 0.7$  ke (~40%)
- After  $2.8 \cdot 10^{15}$  neq/cm<sup>2</sup>: signal-to-noise ratio  $12.3 \pm 0.1$

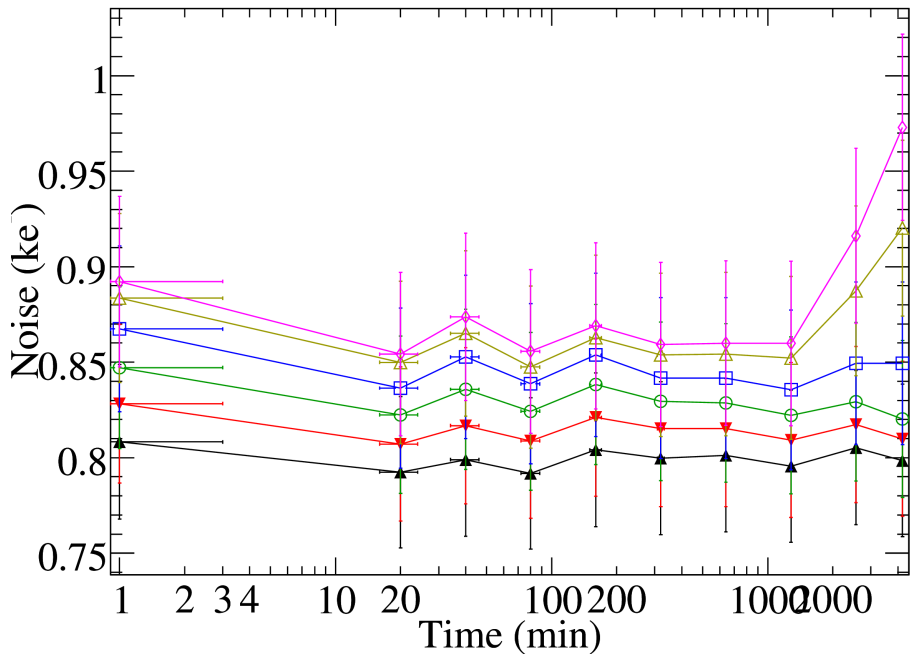


- Different steps of annealing visible
- Collected charge stable until 320 min (~120 days at room temperature) – no reverse annealing
- Enhancement of charge multiplication after 2560 min for voltages above 800 V

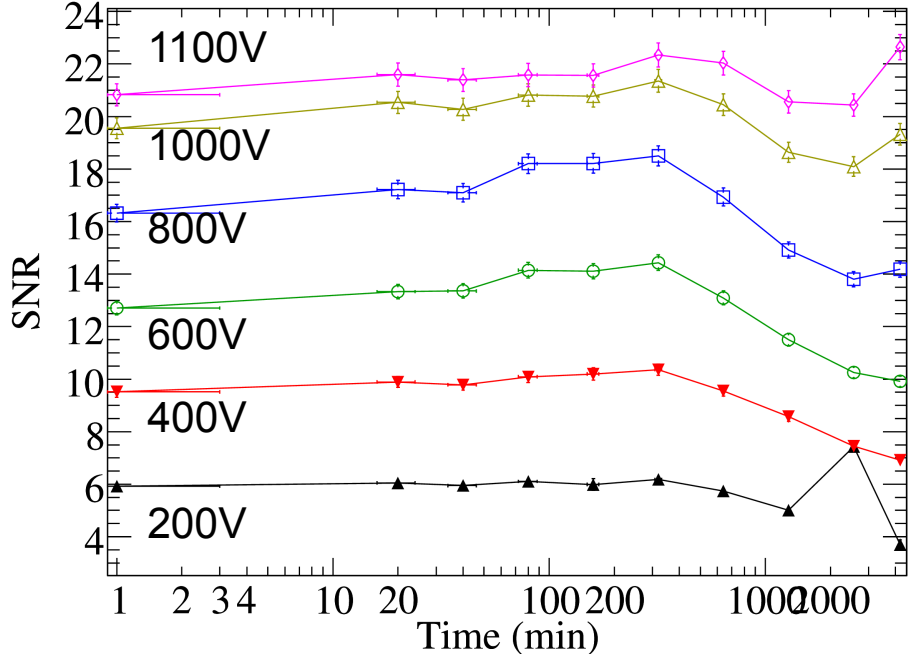
# Annealing studies after $2.1 \cdot 10^{15}$ neq/cm<sup>2</sup>



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Noise



SNR

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